WHAT IS CLAIMED IS:

1. A correction apparatus for correcting a shift between optical axes in two separate optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising:

a converter for converting a positional shift between the optical axes into an angular shift; and an angular corrector for correcting the angular shift.

2. A correction apparatus for correcting a shift between optical paths in two optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising:

a converter for converting a shift between the optical paths into an angular shift; and

an angular corrector for correcting the angular shift.

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- 3. A correction apparatus for correcting a shift between optical axes in two separate optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising:
- a first angular corrector for correcting an angular shift between the optical axes;

a	converter for converting a positional shift
between the	optical axes into an angular shift; and
a	second angular corrector for correcting the
converted angular shift.	

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- 4. A correction apparatus according to claim 3, wherein at least one of said first and second angular correctors comprises:
 - a reflective mirror; and
- a tilting mechanism for tilting said reflective mirror with respect to one of said optical axes.
- 5. A correction apparatus according to claim 3, wherein at least one of said first and second angular correctors comprises:
 - an optical member using total reflection utilizing a difference between refractive indexes; and
 - a tilting mechanism for tilting said optical member with respect to one of said optical axes.

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- 6. A correction apparatus according to claim 3, further comprising:
- a first detector for detecting the angular shift between the optical axes;
- a second detector for detecting the converted angular shift corresponding to the positional shift between the optical axes; and

a controller, connected to said first and second detectors, which controls said first and second angular correctors based on detection results from said first and second detectors.

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7. A correction apparatus according to claim 6, wherein at least one of said first and second angular correctors comprises:

a reflective mirror; and

a drive unit for driving said reflective mirror so that said reflective mirror may tilt with respect to one of said optical axes,

wherein said controller controls said drive unit.

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8. An exposure apparatus comprising:

a correction apparatus for correcting a shift between optical axes in two separate optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising a converter for converting a positional shift between the optical axes into an angular shift, and an angular corrector for correcting the angular shift a light source in the one unit; and

an optical system in the other unit, that
25 projects a pattern formed on a reticle or mask onto an
object to be exposed with light from said light source.

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9. An exposure apparatus comprising:

a correction apparatus for correcting a shift between optical paths in two optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising a converter for converting a shift between the optical paths into an angular shift, and an angular corrector for correcting the angular shift a light source in the one unit; and

an optical system in the other unit, that projects a pattern formed on a reticle or mask onto an object to be exposed with light from said light source.

10. An exposure apparatus comprising:

a correction apparatus for correcting a shift

between optical axes in two separate optical units adapted

such that a beam emitted from one unit enters the other,

said correction apparatus comprising a first angular

corrector for correcting an angular shift between the

optical axes, a converter for converting a positional shift

between the optical axes into an angular shift, and a second

angular corrector for correcting the converted angular

shift a light source in the one unit; and

an optical system in the other unit, that projects a pattern formed on a reticle or mask onto an object to be exposed with light from said light source.

11. A device fabricating method comprising the steps of:

exposing an object to be exposed using an exposure apparatus comprising a correction apparatus for correcting a shift between optical axes in two separate optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising a converter for converting a positional shift between the optical axes into an angular shift, and an angular corrector for correcting the angular shift, and an optical system for projecting a pattern formed on a reticle or mask onto the object to be exposed; and

performing predetermined processes for the object exposed.

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12. A device fabricating method comprising the steps of:

exposing an object to be exposed using an exposure apparatus comprising a correction apparatus for correcting a shift between optical paths in two optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising a converter for converting a shift between the optical paths into an angular shift, and an angular corrector for correcting the angular shift, and an optical system for projecting a pattern formed on a reticle or mask onto the object to be exposed; and

performing predetermined processes for the object exposed.

13. A device fabricating method comprising the5 steps of:

exposing an object to be exposed using an exposure apparatus comprising a correction apparatus for correcting a shift between optical axes in two separate optical units adapted such that a beam emitted from one unit enters the other, said correction apparatus comprising a first angular corrector for correcting an angular shift between the optical axes, a converter for converting a positional shift between the optical axes into an angular shift, and a second angular corrector for correcting the converted angular shift, and an optical system for projecting a pattern formed on a reticle or mask onto the object to be exposed; and

performing predetermined processes for the object exposed.

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